

System and Method for Temperature Measurement, and Calibration Method

Abstract

The present invention relates to a system (1) and a method
5 (100) for temperature measurement in a process chamber (2) of
a high-temperature furnace (50) for workpiece processing, more
particularly semiconductor processing, and to a calibration
method (200) for at least one temperature measurement means
(8) of a high-temperature furnace (50). The process chamber
10 (2) here has an opening (3). The invention provides a
measuring device (4) arranged in front of the opening (3), for
contactlessly determining a temperature (T) within the process
chamber (2) through the opening (3).

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Figure 1